

Notice of References Cited	Application/Control No. 09/096,858		Applicant(s)/Patent Under Reexamination NARWANKAR ET AL.	
	Examiner Anh D. Mai		Art Unit 2814	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-Pub-2001/0011740	08-2001	DeBoer et al.	257/306
	C	US-			
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	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	S.C. Sun et al., A Novel Approach for Leakage Current Reduction of LPCVD Ta2O5 and TiO2 Films by Rapid Thermal N2O Annealing. IEDM 1994, pp. 333-336.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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